

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE



In Re the Application of

KOLESNYCHENKO et al.

Application No.: 10/823,777

Group Art Unit: 1756

Filed: April 14, 2004

Examiner: Unassigned

Confirmation No.: 4703

For: LITHOGRAPHIC APPARATUS AND DEVICE MANUFACTURING METHOD

September 8, 2004

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 C.F.R. 1.56, the attention of the Patent and Trademark Office is hereby directed to the following U.S. patent application(s):

Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
	DE SMIT (081468-0309173)	10/820,227	04/08/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	DE SMIT (081468-0309978)	10/860,662	06/04/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	DUINEVELD et al. (081468-0308101)	10/773,461	02/09/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	FLAGELLO et al. (081468-0302644)	10/698,012	10/31/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	DE SMIT et al. (081468-0306530)	10/705,804	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	LOF et al. (081468-0306781)	10/705,805	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	LOF et al. (081468-0306524)	10/705,783	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card



Examiner's Initials	First Inventor	Application No.	Filing Date	Enclosed
	VAN SANTEN et al. (081468-0307331)	10/743,271	12/23/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	MULKENS et al. (081468-0307333)	10/743,266	12/23/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	DERKSEN et al. (081468-0306526)	10/705,785	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	SIMON et al. (081468-0307087)	10/724,402	12/01/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	BLEEKER (081468-0306527)	10/715,116	11/18/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	STREEFKERK et al. (081468-0306882)	10/719,683	11/24/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	LOF et al. (081468-0306525)	10/705,816	11/12/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	DIERICHS (081468-0308270)	10/775,326	02/11/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	LOF et al. (081468-0309957)	10/857,614	06/01/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card
	SUWA et al. (Reissue Application of U.S. Patent No. 6,191,429 B1)	10/367,910	02/19/2003	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input type="checkbox"/> Other: stamped receipt card
	ZAAL et al. (081468-0309012)	10/814,815	04/01/2004	<input checked="" type="checkbox"/> Specification <input checked="" type="checkbox"/> Drawings <input checked="" type="checkbox"/> Other: stamped receipt card

*The Examiner's initials adjacent a citation indicates he/she has considered the cited application relative to the subject application.

It is respectfully requested that these applications and the art cited therein during examination be expressly considered during the prosecution of this application and be made of record in this application. The identification of the above U.S. patent applications is not to be construed as a waiver of secrecy as to those applications now or upon issuance of the present application as a patent.

PLEASE DO NOT PRINT the above information on the patent which results from this application.

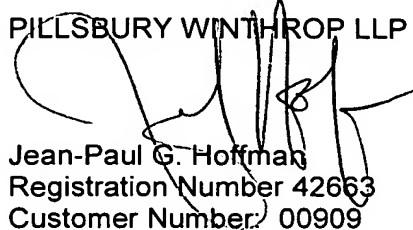
Consideration of each listed application is earnestly solicited since unpublished patent applications are contemplated as IDS material; see the exception in Rule 98(a)(2)(iii) and note the penultimate sentence of MPEP 609.

Further, in keeping with MPEP 609, subsec. C(2), 2nd para., line 10 to end of the paragraph (especially note lines 18-25) PLEASE RETURN A COPY OF THIS LETTER with the Examiner's initials adjacent each above listing so that applicant will know that each listed application has been considered as required by PTO policy.

Secondly, please consider each document which is listed on the attached Form PTO-1449 and return a copy of that form with the Examiner's initials adjacent each citation, a copy of each document enclosed except for any U.S. patents and published patent applications. It is respectfully requested that these documents listed on the Form PTO-1449 be expressly considered during the prosecution of this application, and that the documents be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

This Information Disclosure Statement is being filed before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

Respectfully Submitted,

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FORM PTO-1449 (modified)
 To: U.S. Department of Commerce
 (PW FORM PAT-1449)
 Patent and Trademark Office



**INFORMATION DISCLOSURE STATEMENT
BY APPLICANT**

Date: September 8, 2004

Page **1** of **4**

Atty. Dkt. No.	M#	Client Ref.
	309196	P-1851.000-US
Applicant: KOLESNYCHENKO et al.		
Appln. No. 10/823,777		
Filing Date: April 14, 2004		
Examiner: Unknown		Group Art Unit: 1756

U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
AR	3,573,975	04/1971	DHAKA et al.	117	212	
BR	3,648,587	03/1972	STEVENS	95	44	
CR	4,346,164	08/1982	TABARELLI et al.	430	311	
DR	4,390,273	06/1983	LOEBACH et al.	355	125	
ER	4,396,705	08/1983	AKEYAMA et al.	430	326	
FR	4,480,910	11/1984	TAKANASHI et al.	355	30	
GR	4,509,852	04/1985	TABARELLI et al.	355	30	
HR	5,040,020	08/1991	RAUSCHENBACH et al.	355	53	
IR	5,121,256	06/1992	CORLE et al.	359	664	
JR	5,610,683	03/1997	TAKAHASHI	355	53	
KR	5,715,039	02/1998	FUKUDA et al.	355	53	
LR	5,825,043	10/1998	SUWA	250	548	
MR	5,900,354	05/1999	BATCHELDER	430	395	
NR	6,191,429	02/2001	SUWA	250	548	

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					Enclosed	No	Enclosed	No
OR	WO 99/49504	09/1999	PCT	FUKAMI et al.		X		X
PR	EP 0023231	02/1981	EUROPE	TABARELLI et al.		X		
QR	EP 0418427	03/1991	EUROPE	MIYAKE		X		X
RR	EP 1039511	09/2000	EUROPE	MURAKAMI et al.		X		X
SR	DD 224448	07/1985	GERMANY	HESSE et al.			X	
TR	DD 242880	02/1987	GERMANY	KUCH			X	
UR	FR 2474708	07/1981	FRANCE	LETELLIER			X	
VR	JP 62-065326	03/1987	JAPAN	MORIUCHI		X		
WR	JP 62-121417	06/1987	JAPAN	NAKAZAWA		X		
XR	JP 63-157419	06/1988	JAPAN	NAKASUJI		X		
YR	JP 04-305915	10/1992	JAPAN	OZEKI et al.		X		
ZR	JP 04-305917	10/1992	JAPAN	OZEKI et al.		X		
AAR	JP 06-124873	05/1994	JAPAN	TAKAHASHI		X		X

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BBR	M. SWITKES et al., "Immersion Lithography at 157 nm", MIT Lincoln Lab, Orlando 2001-1, December 17, 2001		
CCR	M. SWITKES et al., "Immersion Lithography at 157 nm", J. Vac. Sci. Technol. B., Vol. 19, No. 6, November/December 2001, pp. 2353-2356		
DDR	M. SWITKES et al., "Immersion Lithography: Optics for the 50 nm Node", 157 Anvers-1, September 4, 2002		

Examiner

Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

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Page 2 of 4

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U.S. PATENT DOCUMENTS

Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
AR	6,560,032	05/2003	HATANO	359	656	
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ER	2002/0163629	11/2002	SWITKES et al.	355	53	
FR	2003/0123040	07/2003	ALMOGY	355	69	
GR	2003/0174408	09/2003	ROSTALSKI et al.	359	642	
HR	2004/0000627 A1	01/2004	SCHUSTER			
IR	2004/0021844 A1	02/2004	SUENAGA			
JR	2004/0075895 A1	04/2004	LIN	359	380	
KR	2004/0109237 A1	06/2004	EPPEL et al.			

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					Enclosed	No	Enclosed	No
LR	JP 07-220990	08/1995	JAPAN	FUKUDA et al.	X			
MR	JP 10-228661	08/1998	JAPAN	KUROKAWA	X			
NR	JP 10-255319	09/1998	JAPAN	SUENAGA et al.	X			
OR	JP 10-303114	11/1998	JAPAN	SUWA	X		X	
PR	JP 10-340846	12/1998	JAPAN	KUDO	X		X	
QR	JP 2001-091849	04/2001	JAPAN	AIZAKI et al.	X			
RR	JP 07-132262	05/1995	Japan	HIRAKAWA et al.	X			
SR	JP 58-202448	11/1983	Japan	KAWAMURA et al.	X			
TR	WO 2004/019128	03/2004	PCT	OMURA et al.	X		X	
UR	WO 03/077037	09/2003	PCT	ROSTALSKI et al.	X		X	
VR	WO 03/077036	09/2003	PCT	SCHUSTER	X			

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WR	B.J. LIN, "Drivers, Prospects and Challenges for Immersion Lithography", TSMC, Inc., September 2002			
XR	B.J. LIN, "Proximity Printing Through Liquid", IBM Technical Disclosure Bulletin, Vol.20, No. 11B, April 1978, p. 4997			
YR	B.J. LIN, "The Paths To Subhalf-Micrometer Optical Lithography", SPIE Vol. 922, Optical/Laser Microlithography (1988), pp. 256-269			
ZR	G.W.W. STEVENS, "Reduction of Waste Resulting from Mask Defects", Solid State Technology, August 1978, Vol.21 008, pp. 68-72			
AAR	S. OWA et al., "Immersion Lithography; its potential performance and issues", SPIE Microlithography 2003, 5040-186, February 27, 2003 .			
BBR	S. OWA et al., "Advantage and Feasibility of Immersion Lithography", Proc. SPIE 5040 (2003)			

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Examiner's Initials*	Document Number	Date MM/YYYY	Name (Family Name of First Inventor)		Class	Sub Class	Filing Date (if appropriate)	
AR	6,236,634 B1	05/2001	LEE et al.		369	112		
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	Document Number	Date MM/YYYY	Country	Inventor Name		Enclosed	No	Enclosed	No
CR	DD 206 607	02/1984	GERMANY	WESTPHAL et al.			X		
DR	DD 221 563	04/1985	GERMANY	PFORR et al.			X		
ER	JP 11-176727	07/1999	JAPAN	SHIRAISHI			X		
FR	JP 2000-058436	02/2000	JAPAN	FUJISHIMA et al.			X		
GR	WO 2004/053950 A1	06/2004	PCT	OWA			X		
HR	WO 2004/053951 A1	06/2004	PCT	MAGOME et al.			X		
IR	WO 2004/053952 A1	06/2004	PCT	MAGOME et al.			X		
JR	WO 2004/053953 A1	06/2004	PCT	NEI et al.			X		
KR	WO 2004/053954 A1	06/2004	PCT	NEI et al.			X		
LR	WO 2004/053955 A1	06/2004	PCT	HIRUKAWA et al.			X		
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NR	WO 2004/053957 A1	06/2004	PCT	HIDAKA et al.			X		
OR	WO 2004/053958 A1	06/2004	PCT	MIZUTANI et al.			X		
PR	WO 2004/053959 A1	06/2004	PCT	SHIRAI			X		
QR	WO 2004/05396 A2	06/2004	PCT	GRAUPNER			X		

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RR	Nikon Precision Europe GmbH, "Investor Relations – Nikon's Real Solutions", May 15, 2003
SR	H. KAWATA et al., "Optical Projection Lithography using Lenses with Numerical Apertures Greater than Unity", Microelectronic Engineering 9 (1989), pp. 31-36
TR	J.A. HOFFNAGLE et al., "Liquid Immersion Deep-Ultraviolet Interferometric Lithography", J. Vac. Sci. Technol. B., Vol. 17, No. 6, November/December 1999, pp. 3306-3309
UR	B.W. SMITH et al., "Immersion Optical Lithography at 193nm", FUTURE FAB International, Vol. 15, July 11, 2003
VR	H. KAWATA et al., "Fabrication of 0.2μm Fine Patterns Using Optical Projection Lithography with an Oil Immersion Lens", Jpn. J. Appl. Phys. Vol. 31 (1992), pp. 4174-4177
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XR	H. HOGAN, "New Semiconductor Lithography Makes a Splash", PHOTONICS SPECTRA, Photonics TechnologyWorld, October 2003 Edition, pgs. 1-3
YR	S. OWA and N. NAGASAKA, "Potential Performance and Feasibility of Immersion Lithography", NGL Workshop 2003, July 10, 2003, Slide Nos. 1-33.

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Page 4 of 4

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ZR	2004/0119954	06/2004	KAWASHIMA et al.	355	30	
AAR	2004/0125351	07/2004	KRAUTSCHIK et al.	355	53	
BBR						
CCR						
DDR						
EER						
FFR						
GGR						
HHR						

FOREIGN PATENT DOCUMENTS

	Document Number	Date MM/YYYY	Country	Inventor Name	English Abstract		Translation Readily Available	
					Enclosed	No	Enclosed	No
IIR	WO 2004/055803 A1	07/2004	PCT	VAN SANTEN	X		X	
JJR	WO 2004/057589 A1	07/2004	PCT	NEIJZEN et al.	X		X	
KKR	WO 2004/057590 A1	07/2004	PCT	VAN SANTEN et al.	X		X	
LLR	JP 2004-193252	07/2004	Japan	Not Available	X			
MMR								
NNR								
OOR								
PPR								

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

QQR	S. OWA et al., "Update on 193nm immersion exposure tool", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-51			
RRR	H. HATA, "The Development of Immersion Exposure Tools", Litho Forum, International SEMATECH, Los Angeles, January 27-29, 2004, Slide Nos. 1-22			
SSR	T. MATSUYAMA et al., "Nikon Projection Lens Update", SPIE Microlithography 2004, 5377-65, March, 2004			
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UUR	A. SUZUKI, "Lithography Advances on Multiple Fronts", EEdesign, EE Times, January 5, 2004			
VVR	B. LIN, "The k_3 coefficient in nonparaxial λ/NA scaling equations for resolution, depth of focus, and immersion lithography, J. Microlith., Microfab., Microsyst. 1(1):7-12 (2002)			
WWI				
XXR				
YYR				
ZZR				
AAA				

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